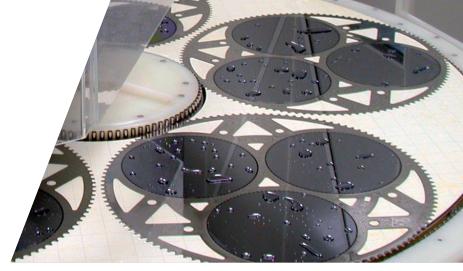




AC microLine® 2000-P3

PRIME WAFER DOUBLE-SIDE POLISHING SYSTEM







THE MOST COMPREHENSIVE SOLUTION

- Unique and patented UPAC (Upper Platen Adaptive Control) System
- 2 Gap Sensors
- Benchmark in precision, quality, efficiency, and cost of ownership
- The most flexible machine for supporting all future wafer requirements

BENCHMARK IN PRECISION AND FLEXIBILITY

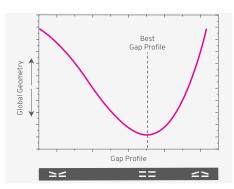




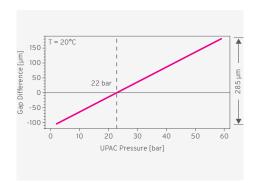
HIGHLIGHTS AC microLine® 2000-P3

- Unique and patented UPAC (Upper Platen Adaptive Control) System
- Monitoring of the cooling lubricant flow rate
- Loop control

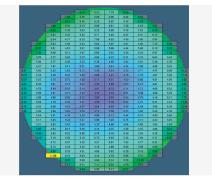
- First-Class customer support for the highest machine availability and productivity
- Integrated high precision interferometric device for in-situ measurement of the wafer thickness
- High-Pressure Conditioner
- Slurry Recycling Station
- Slurry Pressure Distribution
- Integrated Process Data Recording (DataCare®)
- Industry 4.0
- Touch Screen



The importance of the gap – Perfect wafer flatness requires gap adjustment



UPAC System - Global Measurement



SFQR Map - 300 mm Si-Wafer SFQR Values: Max: 11.59 nm, Average: 5.98 nm

TECHNICAL DATA	AC microLine® 2000-P ³
Wheel diameter [mm]	1935
Ring width [mm]	686
Max. load pressure [daN]	4000
Upper/lower drive power [kW]	46
Upper/lower drive speed [rpm]	0-40
Center drive power [kW]	7.5
Center drive speed [rpm]	0-50
Outer drive power [kW]	9.5
Outer drive speed [rpm]	0-7.5
Working wheel cooling	Labyrinth
Dimensions [H×W×D] [mm]	3000×4200×3900
Weight [kg]	21000
Load capacity 300 mm [12"] Wafer 200 mm [8"] Wafer	15 pieces 30 pieces

GET IN TOUCH WITH US TODAY

TOGETHER WE WILL FIND A SOLUTION FOR YOUR REQUIREMENTS

LAPMASTER WOLTERS GMBH

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